ABSTRACT

The apparatus comprises a substrate stage (WST) to mount a substrate (W) and a substrate carriage system (100) to carry a substrate to the substrate stage. The substrate carriage system includes a rotation table (42) that holds and moves the substrate in the X direction and a control system that detects the positional deviation of the substrate W rotating together with the rotation table (42) by using sensors (48) while moving in the X direction. Since the detection of the positional deviation of the substrate overlaps with the time the substrate is being carried, it improves the throughput, as well as improves the space efficiency since exclusive space for detection of the positional deviation is not required. Accordingly, this can reduce the manufacturing cost of devices such as semiconductor devices.